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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re patent application of

Docket No.: FIS920030183US1

Dureseti Chidambarao, et al.

Serial No.: 10/605,108

Group Art Unit: 2107

Filed: September 9, 2003

Examiner: Pham, Long

For: **METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI ON SIGE  
SUBSTRATE**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**SUBMISSION OF FORMAL DRAWINGS**

Sir:

Submitted herewith, are three (3) sheets of formal drawings comprising figures 1-7 for the above-identified patent application. Please substitute the formal drawings for the drawings which were filed with the application.

Respectfully submitted,

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